

10/568770
IAP20 Rec'd FCT/PTO 21 FEB 2006

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHO ET AL.

Atty. Ref.: 4105-73

Appl. No. Unknown

TC/A.U. Unknown

Filed: February 21, 2006

Examiner: Unknown

For: FERROELECTRIC THIN-FILM PRODUCTION METHOD, VOLTAGE-
APPLICATION ETCHING APPARATUS, FERROELECTRIC CRYSTAL THIN-FILM
SUBSTRATE, AND FERROELECTRIC CRYSTAL WAFER

* * * * *

February 21, 2006

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

PRELIMINARY AMENDMENT

In order to place the above-identified application in better condition for
examination, please amend the application as follows: